

**EAST Search History****EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	375	glass with substrate and roughness with (substrate or glass) and circuit\$4 and electroless and (electrodeposit\$4 or electroplat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 20:11
L3	133	glass with substrate and roughness with (substrate or glass) and circuit\$4 and electroless and (electrodeposit\$4 or electroplat\$4)and cataly\$4 with electroless	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 20:13
L4	25	glass with substrate and roughness with (substrate or glass) with nm and circuit\$4 and electroless and (electrodeposit\$4 or electroplat\$4)and cataly\$4 with electroless	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 20:14
S1	1	2002/0187267	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/07/26 14:20
S2	1	2002/0187267	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 14:20
S3	2	10/580953	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:21

S4	0	(photosens\$4 or photoresist\$4) with novolak with patic\$4 with carbon	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:25
S5	0	(photosens\$4 or photoresist\$4) with novolak with patic\$4 with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:25
S6	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:25
S7	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with convert\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:26
S8	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with conver\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:26
S9	3060	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:26
S10	1319	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:27
S11	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light with ultra with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:27

S12	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light with visible with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:28
S13	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible near light with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:28
S14	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible with novolak near2 epoxy	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:28
S15	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible near light with novolak	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:29
S16	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 ultra with novolak	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:29
S17	1	(photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 ultra	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:29
S18	45	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S19	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with wave	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30

S20	20	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S21	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and electroless	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S22	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and plating	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S23	20	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and pattern \$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:30
S24	129	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with (carbon or metal) and pattern \$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:35
S25	1	(photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with (carbon or metal)with(powder or particle or particulate) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:35
S26	213	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:36

S27	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate)with absop \$4 and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:36
S28	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((carbon or metal)near (powder or particle or particulate) with absop \$4 and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:37
S29	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron) near(powder or particle or particulate) with absop\$4 and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:38
S30	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye)near(powder or particle or particulate) with absop\$4 with (ultra or UV) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:40
S31	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (ultra or UV) and pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:40

S32	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (ultra or UV)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:40
S33	0	(photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (infra or ir)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:41
S34	0	(photosens\$4 or photoresist\$4 or photo near resist\$4 or novolak) with(carbon or metal)near(powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (infra or ir)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:41
S35	0	(photosens\$4 or photoresist\$4 or photo near resist\$4 or novolak) with(carbon or metal)near(powder or particle or particulate))and ((iron or metal or silver or pigment or dye or carbon)near(powder or particle or particulate) with absop \$4 with (infra or ir)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:41

S36	0	(photosens\$4 or photoresist\$4 or photo near resist\$4 or novolak) with(carbon or metal)near(powder or particle or particulate))and ((iron or metal or silver or pigment or dye or carbon)with(powder or particle or particulate) with absop\$4 with (infra or ir)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/26 15:41
S37	3	photoresist with (pigment or dye)near3 absorb\$3 near3(UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:04
S38	3	photoresist with (pigment or dye)near3 absorb\$3 near3(UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:05
S39	2	10/580953	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:06
S40	4	(photoresist or photo near resist\$4 or photo near sensitive)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:07
S41	3	(photoresist or photo near resist\$4 or photo near sensitive)with (pigment or dye or colorant)near3 absorb \$3 near3(ir or infra) and (novolac or novolak)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:08

S42	26	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:10
S43	41	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra) and (novolac or novolak)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 18:26
S44	41	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra) and (novola\$2)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:24
S45	25	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive) same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra) and sulphone and ether and aryl	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:25
S46	2	10/140761	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:27
S47	2	10/378553	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:28

S48	408	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:32
S49	189	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:32
S50	0	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near patten\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:32
S51	12	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near patter\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:33
S52	12	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:33

S53	13	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and (conductor or metal) near pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:33
S54	14	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and (conductor or metal) near pattern\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:35
S55	22	(photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and plating	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/27 19:35
S56	2	"20050175824"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/07/29 15:24
S57	2	10/580953	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/15 13:43
S58	14	"3998602"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/15 13:57

S59	2382	((427/99.5/) or (427/304/) or (427/504/) or (427/97.9/) or (427/437/) or (427/443.1/)).CCLS.	USPAT; USOCR	OR	OFF	2011/11/15 14:02
S60	254	S59 and function\$4 and (polymeriz\$4 or crosslink\$4 or graft\$4)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/11/15 14:03
S61	0	S59 and function\$4 with intercat\$4 and (polymeriz\$4 or crosslink\$4 or graft\$4)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/15 14:03
S62	14	S59 and function\$4 with interact\$4 and (polymeriz\$4 or crosslink\$4 or graft\$4)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/15 14:04
S63	3	"20030132121"	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/15 14:13
S64	3	"20030132121"	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:11
S65	1511	circuit with(Print\$4 or board\$4)and (cataly\$4 or plarimum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:26

S66	529	circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:27
S67	0	circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and funsctional near group	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:27
S68	0	circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and funsctional near group	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:27
S69	95	circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and functional near group	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:28

S70	66	circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and functional near group and copolymer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:28
S71	1	12/729634	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:37
S72	64	"6756286"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:51
S73	2	"20030034869"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/17 13:56
S74	19	"2003013"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:41
S75	3	"20030132121"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:41
S78	1	electroless and electoplatis\$4 and electroless with cataly \$4 with adhes\$4 and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:45

S79	1	electroless and electoplac\$4 and cataly\$4 with adhes\$4 and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:47
S80	6	electroless and electoplac\$4 and cataly\$4 same adhes\$4 and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:48
S81	4	electroless and electoplac\$4 and cataly\$4 with electroless same adhes\$4 and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:49
S82	4	electroless and electoplac\$4 with copper and cataly\$4 with electroless and cataly\$4 with(Poly\$4 or adhes\$4) and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:54
S83	5	electroless and electoplac\$4 and copper and cataly\$4 with electroless and cataly\$4 with(Poly\$4 or adhes\$4) and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:54
S84	5	electroless and electoplac\$4 and copper and (platinum or palladium or cataly\$4) with electroless and (platinum or palladium or cataly\$4) with(Poly\$4 or adhes\$4) and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:55

S85	5	electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with electroless and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4) and circuit\$4 near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:57
S86	7	electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with electroless and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 12:57
S87	12	electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:00
S88	12	electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:00
S89	819	electroless and (electrodeposit\$4 or electroplat\$4) and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:03
S90	389	electroless and (electrodeposit\$4 or electroplat\$4) and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4) and (platinum or palladium or cataly\$4)with electroless	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:03

S91	203	electroless and (electrodeposit\$4 or electroplat\$4) and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)and (platinum or palladium or cataly\$4)with electroless and circuit near(board or integrat \$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:04
S92	145	electroless and (electrodeposit\$4 or electroplat\$4) and (platinum or palladium or cataly\$4) with(adhes \$4)and(platinum or palladium or cataly\$4) with electroless and circuit near(board or integrat\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:06
S93	114	electroless and (electrodeposit\$4 or electroplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:06
S94	26	electroless and (electrodeposit\$4 or electroplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)and substrate with glass and substrate with rough\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:10
S95	3	electroless and (electrodeposit\$4 or electroplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)and substrate with glass and substrate with roughn\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:11

S96	26	electroless and (electrodeposit\$4 or electroplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)and substrate with glass and (glass or substrate) with rough \$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 13:13
S97	2	10/580953	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 18:15
S98	38	stamp\$4 with release same photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/11/18 18:47

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